

Anhydrous Hydrogen Peroxide Gas for Thin Film Processing

Increase surface hydroxylation, lower process temperatures & increase choice in precursors

BRUTE® Peroxide 2.1 is the next generation product from RASIRC® to deliver concentrated hydrogen peroxide (H₂O₂) gas for Atomic Layer Deposition (ALD), Atomic Layer Etch (ALE) and other processes that require controlled delivery of H₂O₂ gas with minimal water. This improved version BRUTE® Peroxide delivers gas from a solid source and has superior output and longer shelf life than previous BRUTE® Peroxides. Design advantages include improved output stability, concentration, purity, and safety. H₂O₂ molecules are pre-loaded onto the proprietary solid sorbent in a engineered vaporizer that is designed specifically for the stable storage and delivery of H₂O₂ gas for high purity applications. Brute® Peroxide 2.1 simplifies having to store or handle high concentration liquid peroxide.

Background

Oxidants such as oxygen, water, oxygen plasma, and ozone have all been used for cleaning, stripping, hydroxylation, and oxidation in thin film processes. However, with shrinking thermal budgets, oxygen and water have lost their effectivity. Ozone and plasma can be difficult to control, can cause surface and subsurface damage, and generate non-uniformities in High Aspect Ratio (HAR) structures.

With BRUTE® Peroxide 2.1, H₂O₂ is now a superior alternative to these older methods. H₂O₂ has a rapid and straightforward reaction pathway. BRUTE® Peroxide overcomes historical concentration control issues of water in the H₂O₂ source.

Typical water/H₂O₂ solutions produce relatively low H₂O₂ gas concentrations. Water has significantly higher vapor pressure compared to H₂O₂. This leads to a high concentration of water in the headspace which is ultimately delivered to the chamber.

Frequently overestimated, the H₂O₂ gas concentration in the headspace above a 30 wt% H₂O₂ solution is only 25 ppm, not 30%. The molar ratio of H₂O₂ to water is 1:181 at 0°C, 760 torr.

Prior to Brute® Peroxide commercialization,

the majority of technical publications frequently concluded that there was minimal process difference between H₂O₂ and water, when in fact, the studies failed to deliver enough H₂O₂ to demonstrate the superiority of H₂O₂ to water in the process.

BRUTE® Peroxide Benefits

- Provides stable delivery of H₂O₂ gas with minimal water.
- Not a nebulizer which delivers liquid droplets of H₂O₂/H₂O which can lead to non-uniformity, spotting and particulates.
- Allows for differentiation between H₂O₂ and water vapor in process reactions.
- Alternative to water, ozone, or oxygen plasma.
- Improves compatibility with metal surfaces—less aggressive oxidant than ozone or Oxygen Plasma
- Enables ambient delivery H₂O₂ gas without the need for additional heating and related decomposition
- Reacts faster and at lower temperatures than water.
- Superior surface density hydroxylation with minimal subsurface oxidation.
- Superior penetration into 3D and HAR microstructures compared to water.
- Allows for high concentration H₂O₂ delivery into vacuum and low-pressure applications.
- Increases interface hydroxyl density on Si, Ge and SiGe films.
- Proprietary delivery process, ensuring higher purity.
- Overcomes Raoult's law to provide constant mass flow rate as source is consumed.



Table 1: P/N: 100955 Ampoule Index

Index	Description	Size/Type
A	Inert Gas Inlet	1/4" Male VCR*
B	Process Gas Outlet	1/4" Male VCR
C	Vent Relief Port	9/16-18UNF
D	Grounding Cable Assembly	18" length of wire with M5 Terminal Ring (included with vaporizer) - Part number 201990

*VCR is registered trademark of Swagelok

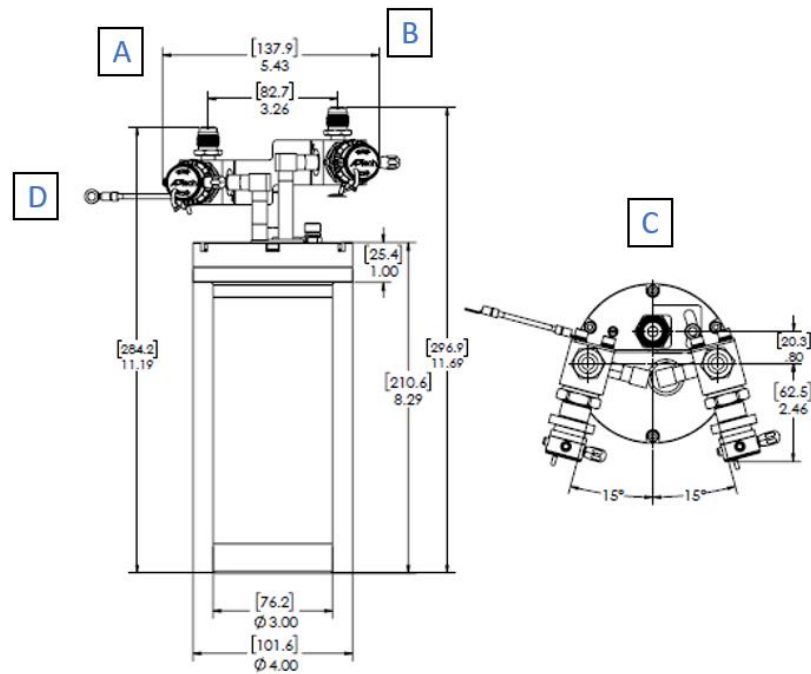


Figure 1: P/N 100955 Ampoule Design, 235 Gram Fill

Table 2: BRUTE® Peroxide vs. H₂O₂/H₂O Solutions

Solution Concentration (weight percent peroxide)	H ₂ O ₂ Concentration (ppm)	H ₂ O Concentration (ppm)
30	203*	24,131*
50	533*	17,143*
70	1,142*	9,241*
BRUTE® Peroxide 2.1	2,248**	1,128**
98	2,452*	421*

*Theoretical values based upon 25C and 760 torr per Raoult's Law.

**Measured at 25C and 760 torr carrier gas flowrate of 1000 SCCM.

Table 3: Specifications

Operating Conditions	<ul style="list-style-type: none"> ○ Temperature: 10-40° C ○ Max Pressure: 1520 torr
Carrier Gas Requirements (If used)	<ul style="list-style-type: none"> ○ 0-2000 sccm (user controlled MFC) STP: 0°C and 760 torr ○ Filtered to 0.003 µm ○ Purified to < 1ppb contaminants ○ CDA, Oxygen, Nitrogen or inert gas
Vaporizer Output	<ul style="list-style-type: none"> ○ ≥10mg/min at 20C and 100 torr with 500 sccm carrier gas
Tools & Supplies Required	<ul style="list-style-type: none"> ○ PPE (see SDS for BRUTE® Peroxide RASIRC® P/N 900966) ○ (2) 1/4" SS VCR gaskets no silver plating (Swagelok PN: SS-4-VCR-2-VS) ○ 3/4" and 5/8" wrenches
Required Facilities	<ul style="list-style-type: none"> ○ Facility approved abatement system for H₂O₂ ○ H₂O₂ safety gas monitor ○ Electrical ground connection ○ Proper ventilation
Shelf Life	<ul style="list-style-type: none"> ○ 12 weeks at 25°C ○ 6 months if stored at 0-10° C
Vent Relief Cracking Pressure	<ul style="list-style-type: none"> ○ Vessel will relieve pressure when above 25.0 psig

How to Order

To place an order for **BRUTE® Peroxide**:

1. Use Table 4 to identify the part number for the desired chemistry weight (g)
2. Contact RASIRC® at sales@rasirc.com

Table 4: BRUTE® Peroxide Chemistry

Name	Mass Loading	Part Number
BRUTE® Peroxide 2.1	235g	110232-235G

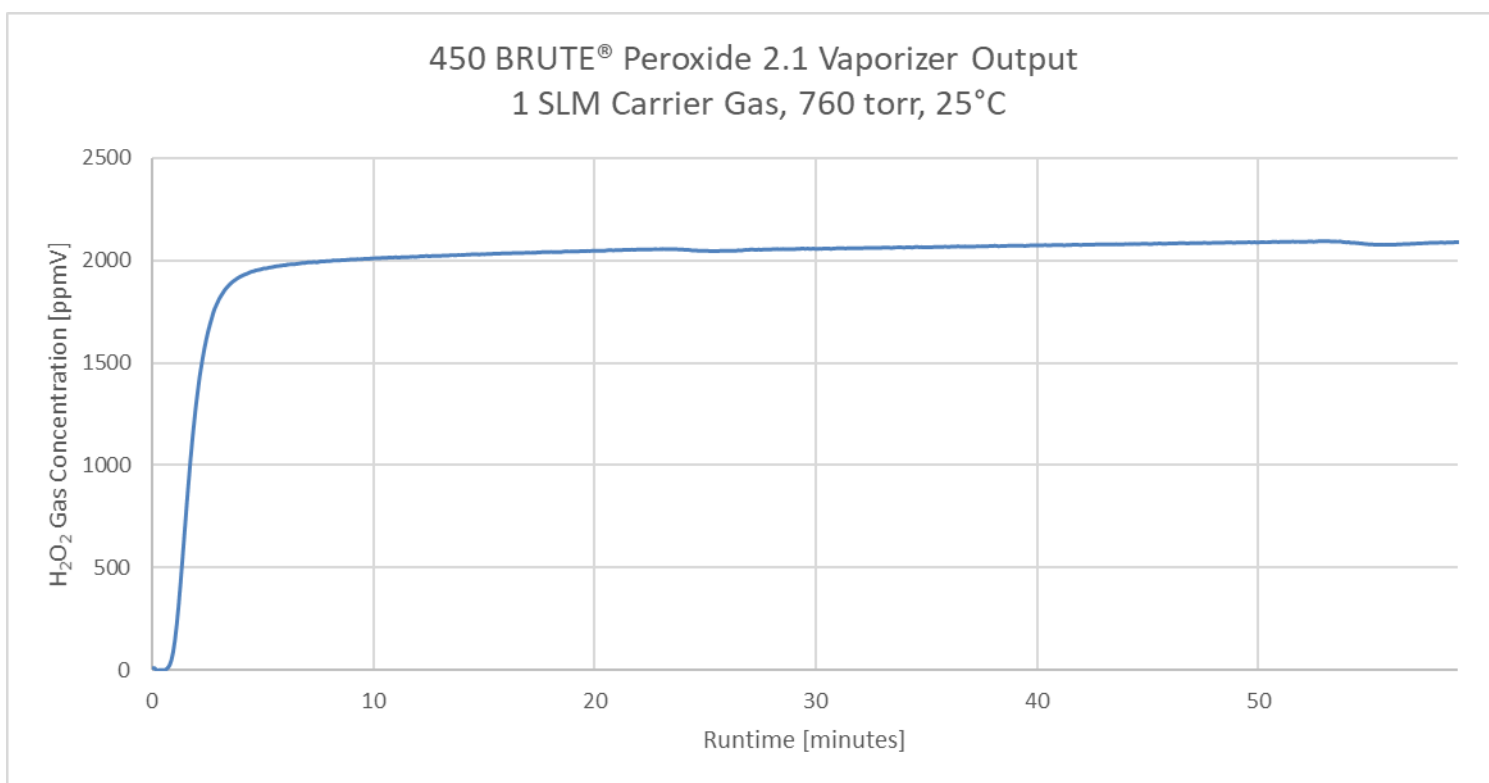


Figure 2: Vaporizer Output of H₂O₂ for BRUTE® Peroxide 2.1



About RASIRC®

RASIRC® products generate and deliver water vapor, hydrogen peroxide and hydrazine gas to enable critical processes.